

attraction electrode. The conductor pattern includes a power supplying terminal formed on the second portion of the first insulating layer. The terminal member includes a contact part which is in contact with the power supplying terminal. The urging unit urges the contact part of the terminal member to the power supplying terminal of the electrostatic chuck. The wiring line is electrically connected to the terminal member. In an embodiment, the wiring line may be electrically connected to the terminal member through the urging unit. The power supply is electrically connected to the wiring line.

[005a] Accordingly, in one aspect of the disclosure, there is provided an electrostatic attraction apparatus comprising: an electrostatic chuck configured to attract and hold a processing target object, the electrostatic chuck including: a base including a first face and a second face different from the first face, a first insulating layer formed on the base and including a first portion extending on the first face and a second portion extending on at least a portion of the second face, an attraction electrode formed on the first portion, a second insulating layer formed on the first portion and the attraction electrode, and a conductor pattern formed on the first insulating layer and electrically connected to the attraction electrode, the conductor pattern including a power supplying terminal formed on the second portion; a terminal member including a contact part contacted to the power supplying terminal; an urging unit configured to urge the contact part of the terminal member to the power supplying terminal; a wiring line electrically connected to the terminal member; and a power supply electrically connected to the wiring line.

[005b] In yet another aspect, there is provided an electrostatic attraction chuck for attracting and holding a processing target object, the chuck comprising: a base including a first face and a second face different from the first face; a first insulating layer formed on the base and

including a first portion extending on the first face and a second portion extending on at least a portion of the second face; an attraction electrode formed on the first portion; a second insulating layer formed on the first portion and the attraction electrode; and a conductor pattern formed on the first insulating layer and electrically connected to the attraction electrode, the conductor pattern including a power supplying terminal formed on the second portion.

[005c] In still another aspect, there is provided a cooling treatment apparatus comprising: a processing container; the electrostatic attraction apparatus as defined herein, the electrostatic chuck being provided within the processing container; and a refrigerator configured to cool the electrostatic chuck.

[0006] The foregoing summary is illustrative only and is not intended to be in any way limiting. In addition to the illustrative aspects, embodiments, and features described above, further aspects, embodiments, and features will become apparent by reference to the drawings and the following detailed description.

BRIEF DESCRIPTION OF THE DRAWINGS

[0007] FIG. 1 is a view schematically illustrating a processing system according to an exemplary embodiment.

[0008] FIG. 2 is a view schematically illustrating a cooling treatment apparatus according to an exemplary embodiment.

[0009] FIG. 3 is a perspective view illustrating an electrostatic attraction apparatus according to an exemplary embodiment.

[0010] FIG. 4 is a cross-sectional view illustrating an electrostatic chuck according to an exemplary embodiment.